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IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re application of:

Chi-Chun Chen et al.

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Docket No.: 24061.461

(2002-0066)

Serial No.: 10/600,393

§

Group Art Unit: 2822

Filed: 06/20/2003

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Examiner: Thomas Toniae M.

For: METHOD OF FORMING DUAL  
GATE INSULATOR LAYERS FOR  
CMOS APPLICATIONS

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Conf. No.: 8529

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TRANSMITTAL

Mail Stop: AMENDMENT

Commissioner for Patents

P.O. Box 1450

Alexandria, VA 22313-1450

Dear Sir:

Enclosed for filing in the above-identified patent application.

1. Amendment in Response to the Office Action dated September 22, 2004;
2. Revocation/New Power of Attorney By Assignee of Entire Interest Including Certification for Taking Action By Assignee Under 37 CFR 3.73(b);
3. Information Disclosure Statement and USPTO Form 1449;
4. Checks in the total amount of \$380.00 (\$200.00 additional independent claim; \$180 IDS);
5. This transmittal (in duplicate); and
6. Return postcard.

The Director is authorized to charge any deficiency fees or credit any overpayments to Deposit Account No. 08-1394 of Haynes and Boone, LLP.

Respectfully submitted,

David M. O'Dell

Registration No. 42,044

Date: 12-22-04

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File: 24061.461

CERTIFICATE OF MAILING

I hereby certify that this correspondence is being deposited with the United States Postal Service as first class mail in an envelope addressed to: Commissioner For Patents, P.O. Box 1450, Alexandria, VA 22313-1450 on the date indicated below:

Bonnie Boyle  
Bonnie Boyle

12-22-04  
Date

